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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Zhu et al.

Attorney Docket No.:
NOVLP090/NVLS-002888

Application No.: 10/733,858

Examiner: Not yet assigned

Filed: December 10, 2003

Group: 2812

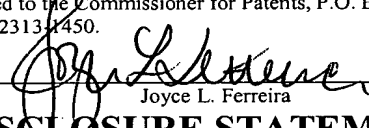
Title: BIASED H₂ ETCH PROCESS IN
DEPOSITION-ETCH-DEPOSITION GAP
FILL

Confirmation No. 7860

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on April 5, 2005 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

Signed: _____


Joyce L. Ferreira**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT
37 CFR §§1.56 AND 1.97(b)**

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

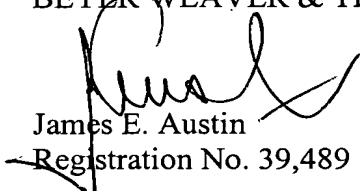
The references listed in the attached PTO Form 1449, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

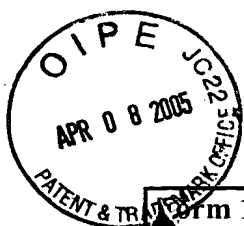
This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP090).

Respectfully submitted,
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Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	<table style="width: 100%;"> <tr> <td style="width: 50%;">Atty Docket No. NOVLP090/NVLS-2888</td> <td style="width: 50%;">Application No.: 10/733,858</td> </tr> <tr> <td colspan="2">Applicant: Zhu et al.</td> </tr> <tr> <td>Filing Date December 10, 2003</td> <td>Group 2812</td> </tr> </table>	Atty Docket No. NOVLP090/NVLS-2888	Application No.: 10/733,858	Applicant: Zhu et al.		Filing Date December 10, 2003	Group 2812
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Applicant: Zhu et al.							
Filing Date December 10, 2003	Group 2812						

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,030,881	02/29/00	Papasouliotis			
	A2	6,265,269	07/24/01	Chen et al.			
	A3	6,277,764	08/21/01	Shin et al.			
	A4	6,335,261	01/01/02	Natzle, et al.			
	A5	6,479,396	11/12/02	Xu et al.			
	A6	6,569,777	05/27/03	Hsu et al.			
	A7	2001-0019903	09/06/01	Shufflebotham et al.			
	A8	2004-0058549	03/25/04	Cai, Yuqi et al.			
	A9	6,867,086	03/15/05	Chen et al.			
	A10	6,531,377	03/11/03	Knorr et al.			
	A11	5,516,729	05/14/96	Dawson et al.			
	A12	6,566,229	05/20/03	Hong et al.			
	A13	6,500,728	12/31/02	Wang			
	A14	6,479,361	11/12/02	Park			
	A15	6,642,105	11/04/03	Kim et al.			
	A16	2003-0087506	05/08/03	Kirchhoff			
	A17	6,596,654	06/22/03	Bayman et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	

Examiner	Date Considered
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.